Please substitute the following amended claims for corresponding claims previously presented. A copy of the amended claims showing current revisions is attached.

1. (Amended) A method of manufacturing a liquid crystal display apparatus having, on one of a pair of substrates disposed so as to be opposed with a liquid crystal layer therebetween, a reflecting film for reflecting incident light from the other substrate, comprising:

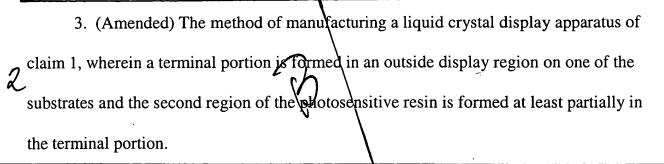
applying a photosensitive resin on said one of the substrates;

in order to form asperities in a first region of the applied photosensitive resin film which do not extend all the way through the photosensitive resin and to form a contact hole in a second region of the applied photosensitive resin film, exposing at least part of the first region with various integrals of exposure amounts so that the photosensitive resin in the first region is left in respective different film thicknesses and exposing at least part of the second region with an integral of exposure amount different from those for the first region;

developing the exposed photosensitive resin;

heat-treating the developed photosensitive resin; and

forming a reflecting film on the heat-treated photosensitive resin so that the reflecting film is in electrical communication with a switching element through said contact hole.



8. (Amended) The method of manufacturing a liquid crystal display apparatus of claim 19, wherein uniform and low-illuminance exposure is performed exposing the photosensitive resin using one of the first photomask and the second photomask, while uniform and high-illuminance exposure is performed at the step of exposing the photosensitive resin using the other of the first photomask and the second photomask.

Please add the following new claims:

11. (New) A method of making a reflective liquid crystal display, the method comprising:

providing a substrate;

applying a photosensitive resin on the substrate;

using a single photomask to form both a) asperities in a first region of the photosensitive resin which do not extend all the way through the photosensitive resin, and b) contact holes in a second region of the photosensitive resin, said contact holes exending all the way through the photosensitive resin;

providing said photomask with light transmitting portions, light intercepting portions, and semi-light transmitting portions, so that different amounts of light exposure are utilized using said photomask in order to form at least one of said asperities and said contact holes;

developing the exposed photosensitive resin;

heat treating the developed photosensitive resin; and

forming a reflective electrode on the heat treated photosensitive resin so that said reflective electrode is in electrical communication with a switching element through at least one of said contact holes.

12. (New) The method of claim 11, wherein the photosensitive resin is negative, and said exposure includes exposing the photosensitive resin using said photomask when the light transmitting portions and semi-light transmitting portions of the mask are located over said first region of said photosensitive resin, and the light intercepting portions of said photomask are located over said second region of said photosensitive resin.

13. (New) The method of claim 11, wherein the photosensitive resin is positive, and said exposure includes exposing the photosensitive resin using said photomask when said light intercepting portions and said semi-light transmitting portions of said photomask are located over said first region of said photosensitive resin, and said light

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transmitting portion of said photomask is located over said second region of said photosensitive resin.

14. (New) A method of making a reflective liquid crystal display, the method comprising:

applying a photosensitive resin to a substrate;

forming asperities which do not extend all the way through the resin in a first region of the photosensitive resin by using a first photomask and exposing at least part of the first region using said first photomask;

forming contact holes in a second region of the photosensitive resin using a second photomask different than the first photomask, and exposing at least part of the second region using said second photomask;

developing the exposed photosensitive resin;

heat treating the developed photosensitive resin; and

forming a reflective electrode on the heat treated photosensitive resin over asperities so that said reflective electrode is in communication with at least one switching element through at least one of the contact holes.

15. (New) The method of claim 14, wherein exposure amounts using the first and second photomasks are the same.

16. (New) The method of claim 14, wherein uniform and low-illuminance exposure is performed so as to expose the photosensitive resin using the first photomask, while uniformed and higher illuminance exposure is performed so as to expose the photosensitive resin using the second photomask.

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17. (New) The method of claim 14, wherein the photosensitive resin comprises a positive photosensitive resin, and the method further comprises removing the photosensitive resin when it is left in the second region after the developing.

18. (New) The method of claim 14, wherein uniform and low-illuminance exposure is performed so as to expose the photosensitive resin using the second photomask, while uniform and higher illuminance exposure is performed so as to expose the photosensitive resin using the first photomask.

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19. (New) A method of manufacturing a liquid crystal display apparatus having, on one of a pair of substrates disposed so as to be opposed with a liquid crystal layer therebetween, a reflecting film for reflecting incident light from the other substrate, comprising:

applying a photosensitive resin on said one of the substrates;

in order to form asperities in a first region of the applied photosensitive resin film which do not extend all the way through the photosensitive resin and to form a contact hole in a second region of the applied photosensitive resin film, exposing at least part of

the first region with various integrals of exposure amounts using a first photomask so that the photosensitive resin in the first region is left in respective different film thicknesses, and exposing at least part of the second region with an integral of exposure amount different from those for the first region using a second photomask;

developing the exposed photosensitive resin;

heat-treating the developed photosensitive resin; and

forming a reflecting film on the heat-treated photosensitive resin so that the reflecting film is in electrical communication with a switching element through said contact hole.

20. (New) A method of manufacturing a liquid crystal display apparatus having, on one of a pair of substrates disposed so as to be opposed with a liquid crystal layer therebetween, a reflecting film for reflecting incident light from the other substrate, comprising:

applying a photosensitive resin on said one of the substrates;

in order to form asperities in a first region of the applied photosensitive resin film which do not extend all the way through the photosensitive resin and to form a contact hole in a second region of the applied photosensitive resin film, exposing at least part of the first region with various integrals of exposure amounts so that the photosensitive resin in the first region is left in respective different film thicknesses, and exposing at least part of the second region with an integral of exposure amount different from those for the first region;